

Graphene-on-Silicon Hybrid Field-Effect Transistors

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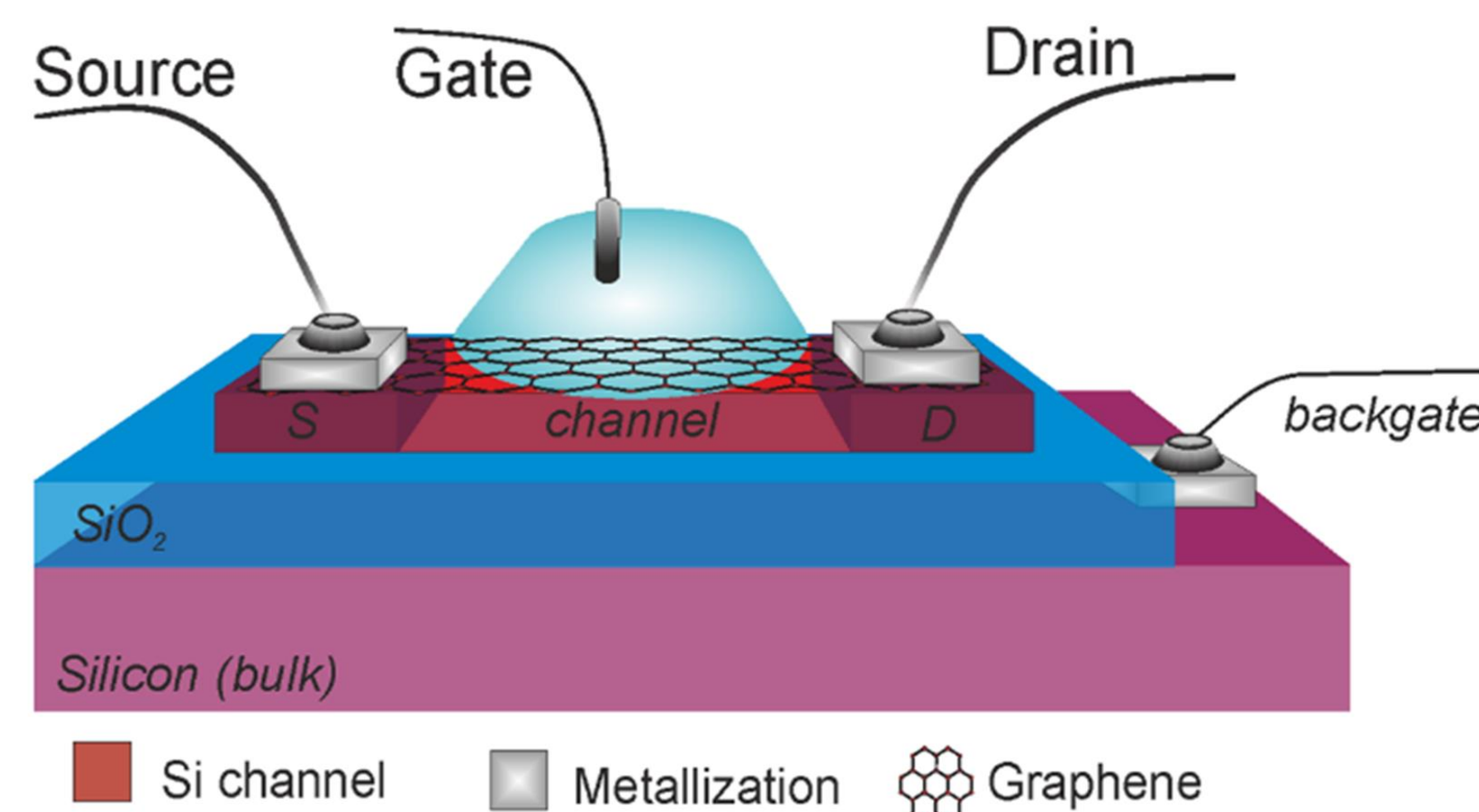
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Motivation

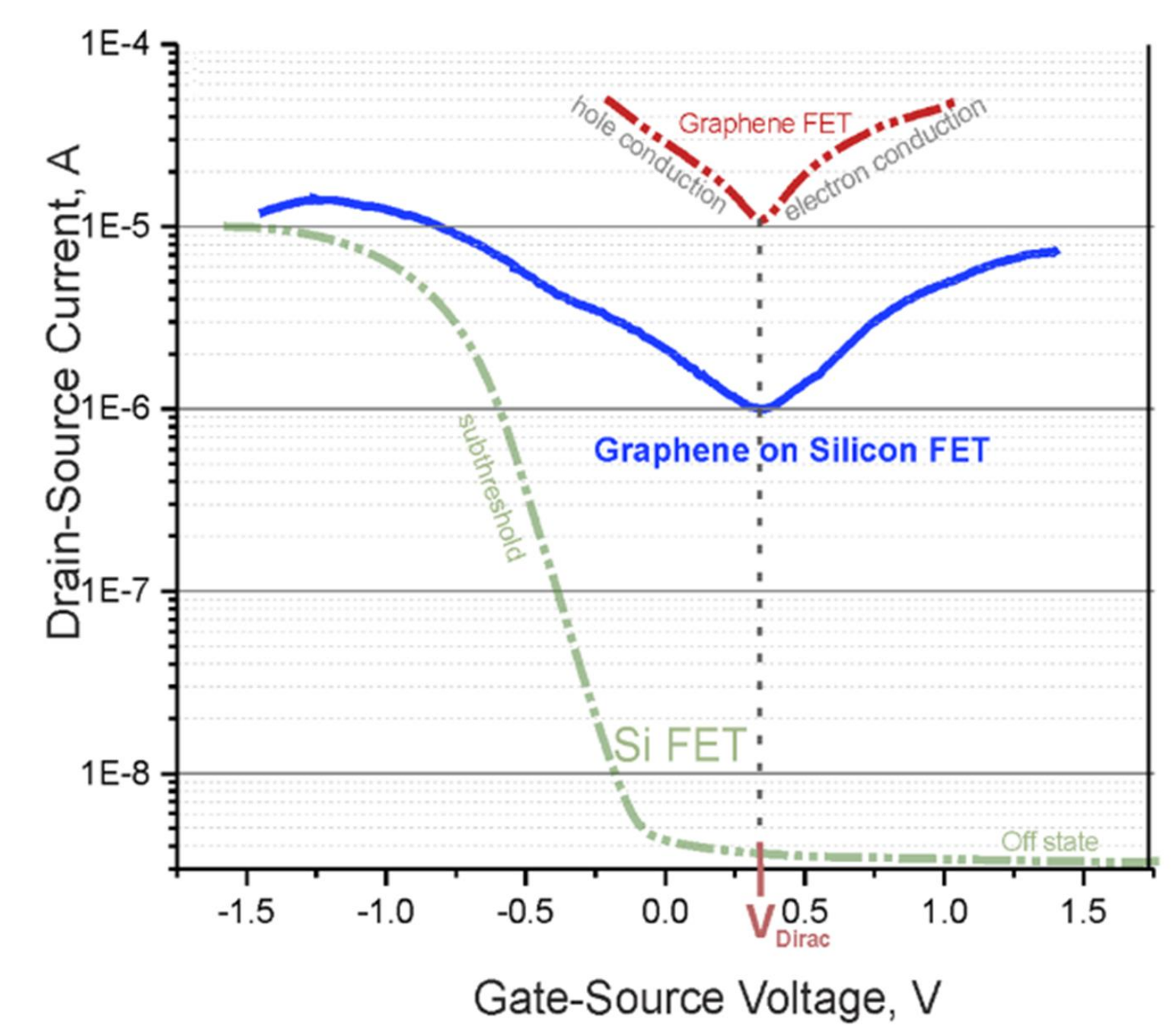
Silicon is an iconic material that has been the cornerstone of micro- and nano- electronics for the last 50 years. Si field-effect transistors (FETs) have been extensively used in biosensing applications [1,2]. However, silicon is known to be a bioresorbable material that gradually degrades when immersed in the electrolyte solution. Therefore, Si FETs suffer from a limited operating time.

Graphene, on the other hand, has not only opened up new prospects in modern nanoelectronics applications, it also has great potential for bio- and neuro-applications as well as being biocompatible and exceptionally stable in electrolytes [3].

In this study, we present a new kind of **graphene-on-silicon (GoS) structure** and use it as a basis for building functional devices, such as **liquid-gated GoS FETs**.



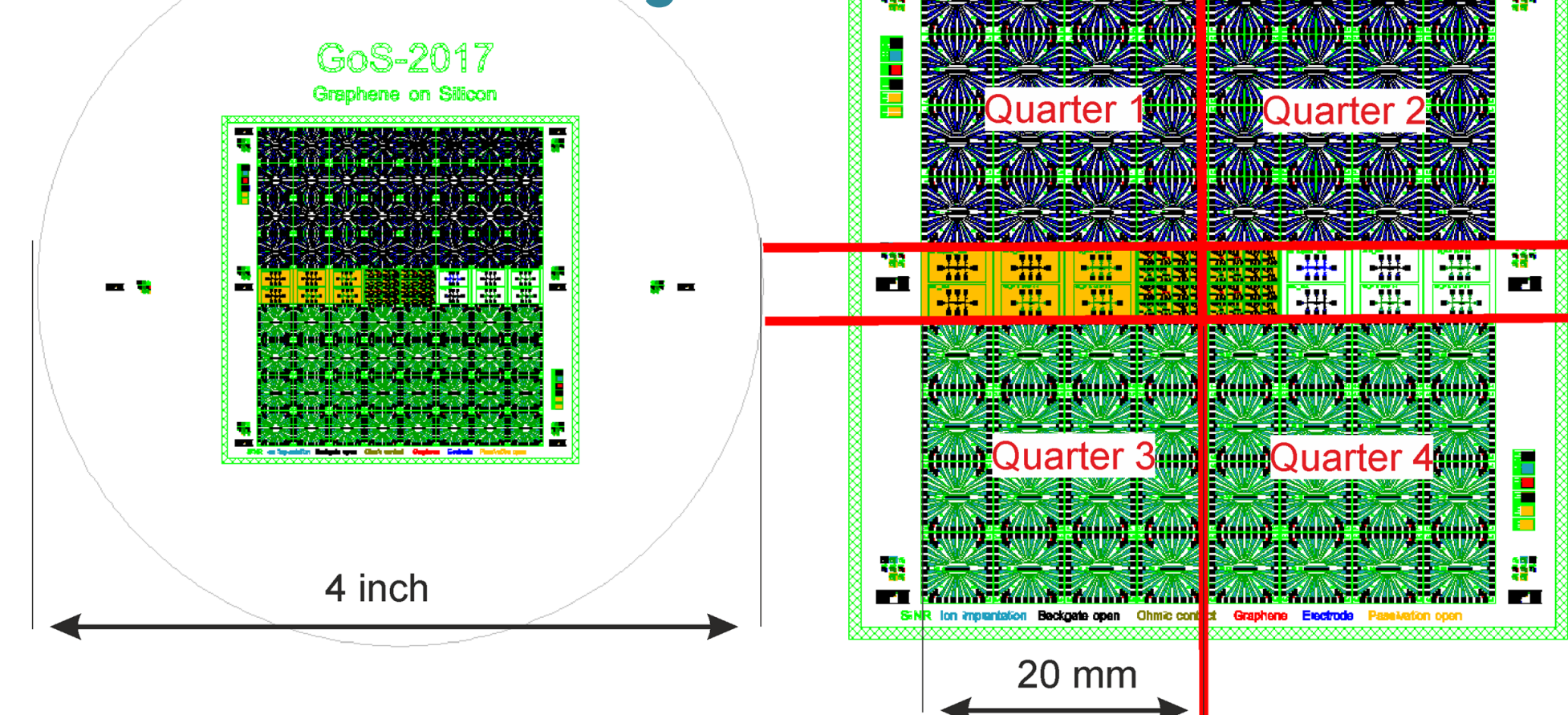
A large variety of devices were fabricated, with a general schematic shown in the Figure, while we varied the widths and lengths of the **graphene and silicon channels** as well as their ratio and level of silicon doping.



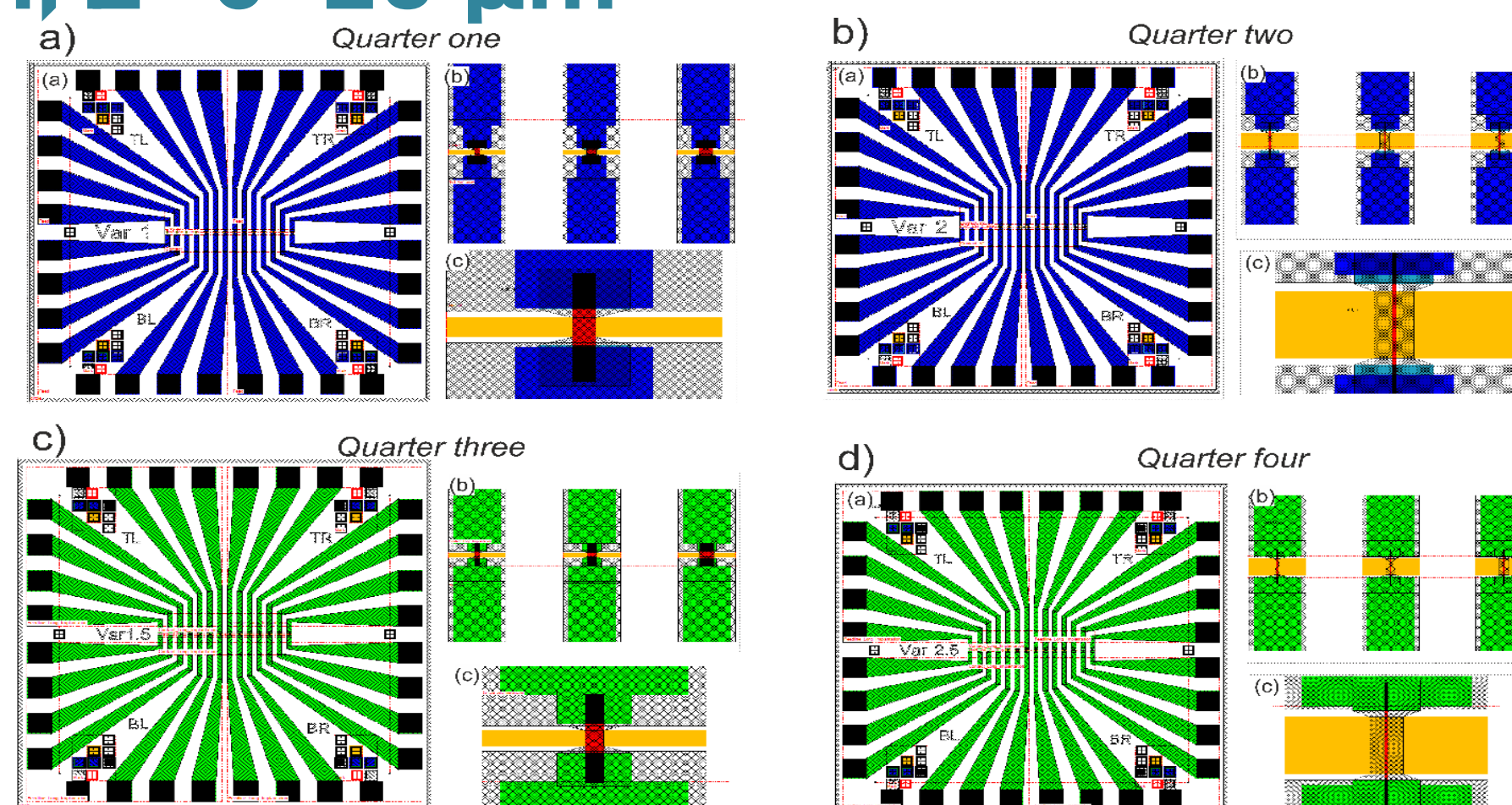
Typical I-V characteristics obtained for bare Si FET, bare G FET, and hybrid GoS-FET structure.

GoS-FETs. Varied the widths and lengths of the graphene and silicon channels: $W = 1-4 \mu\text{m}$, $L = 5-20 \mu\text{m}$

GoS-FETs mask design

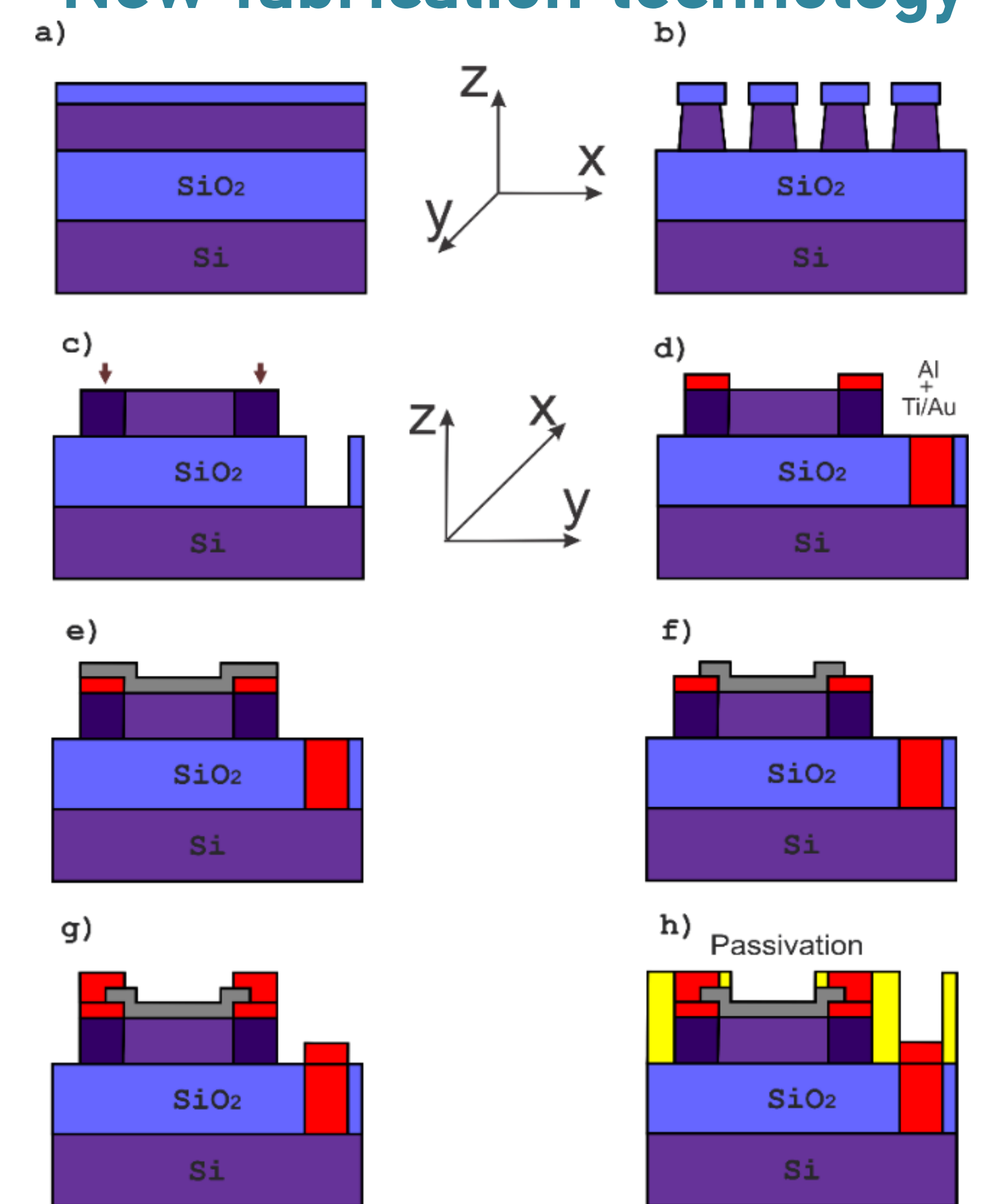


An overview on the whole 4-inch silicon-on-insulator (SOI) wafer with a zoom into the middle region featuring four regions that have different geometries of GoS-FET structures.



Enlarged details of designed GoS-FET devices:
blue – metallization;
white-black squares – silicon meza-structure;
green – ion implantation profile;
yellow – passivation openings.

New fabrication technology

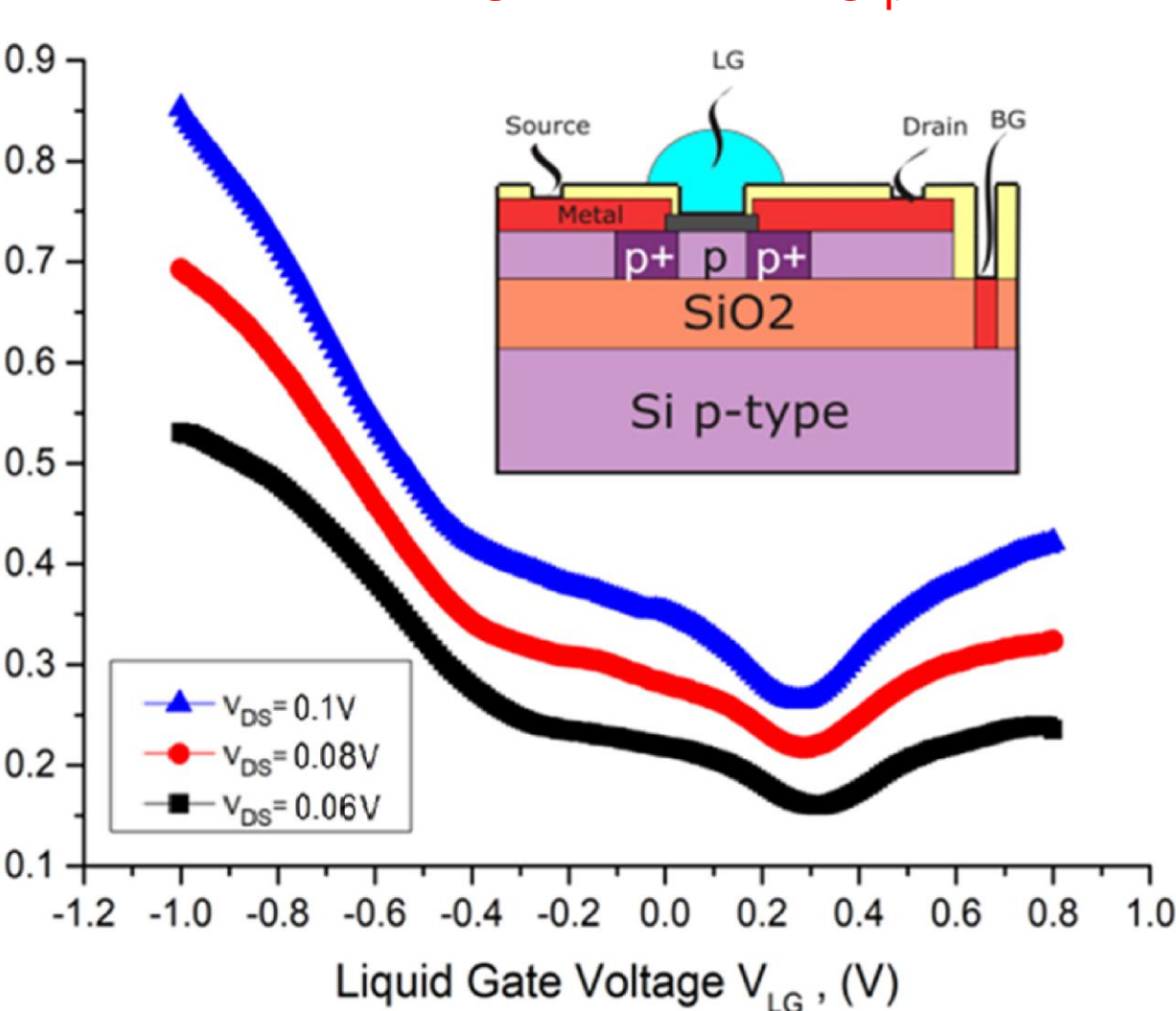
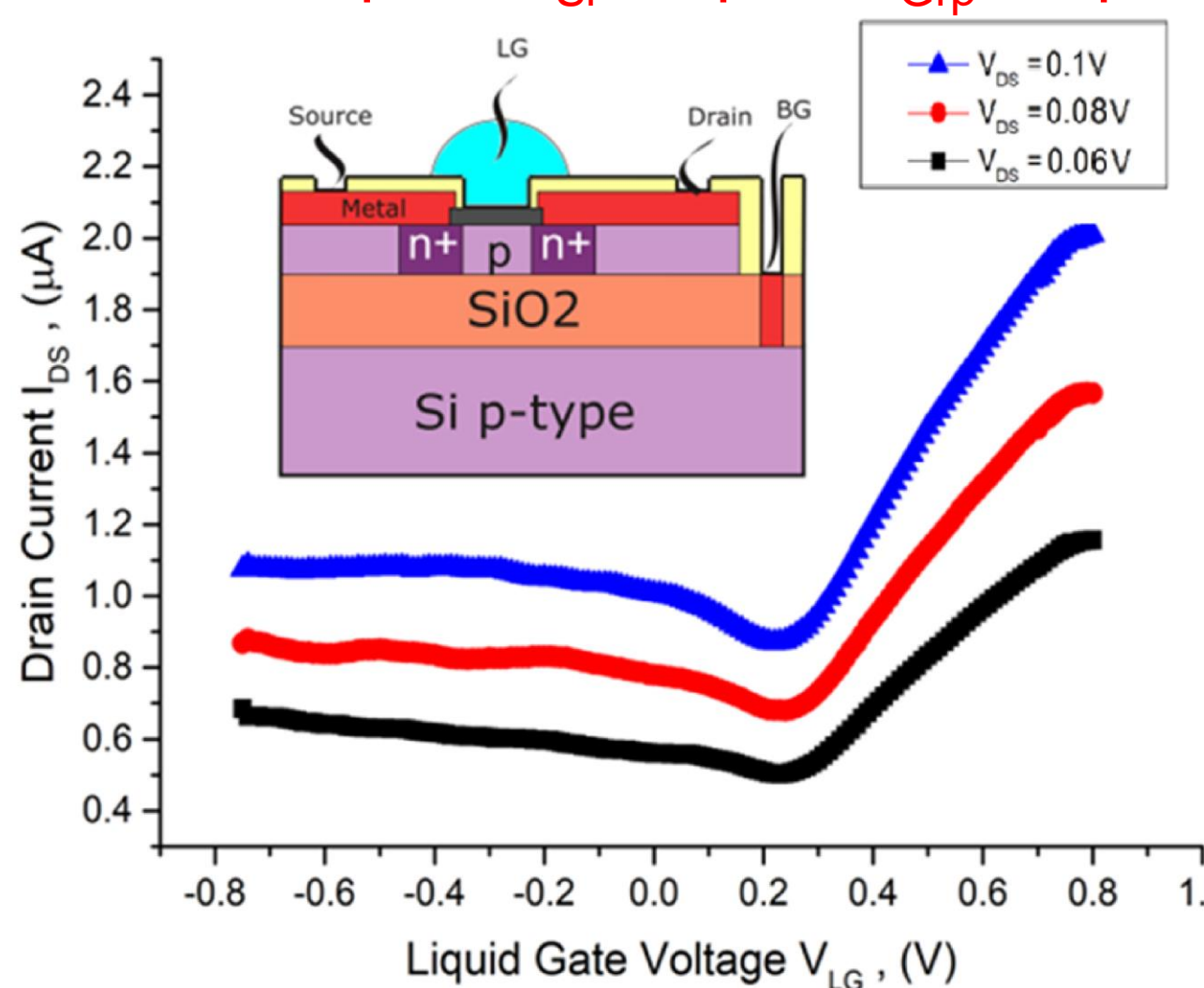


- SOI wafer with SiO₂ hard mask on the top
- Etched silicon working area, through the patterned hard mask for Si ribbons
- Ion implantation and back gate opening etching
- Metallization
- e-f) Graphene transfer and patterning
- Second metallization
- Passivation

Liquid-gated GoS-FETs: Experimental Results and Discussion

$L = 20 \mu\text{m}$; $W_{Si} = 5 \mu\text{m}$; $W_{Grp} = 2 \mu\text{m}$;

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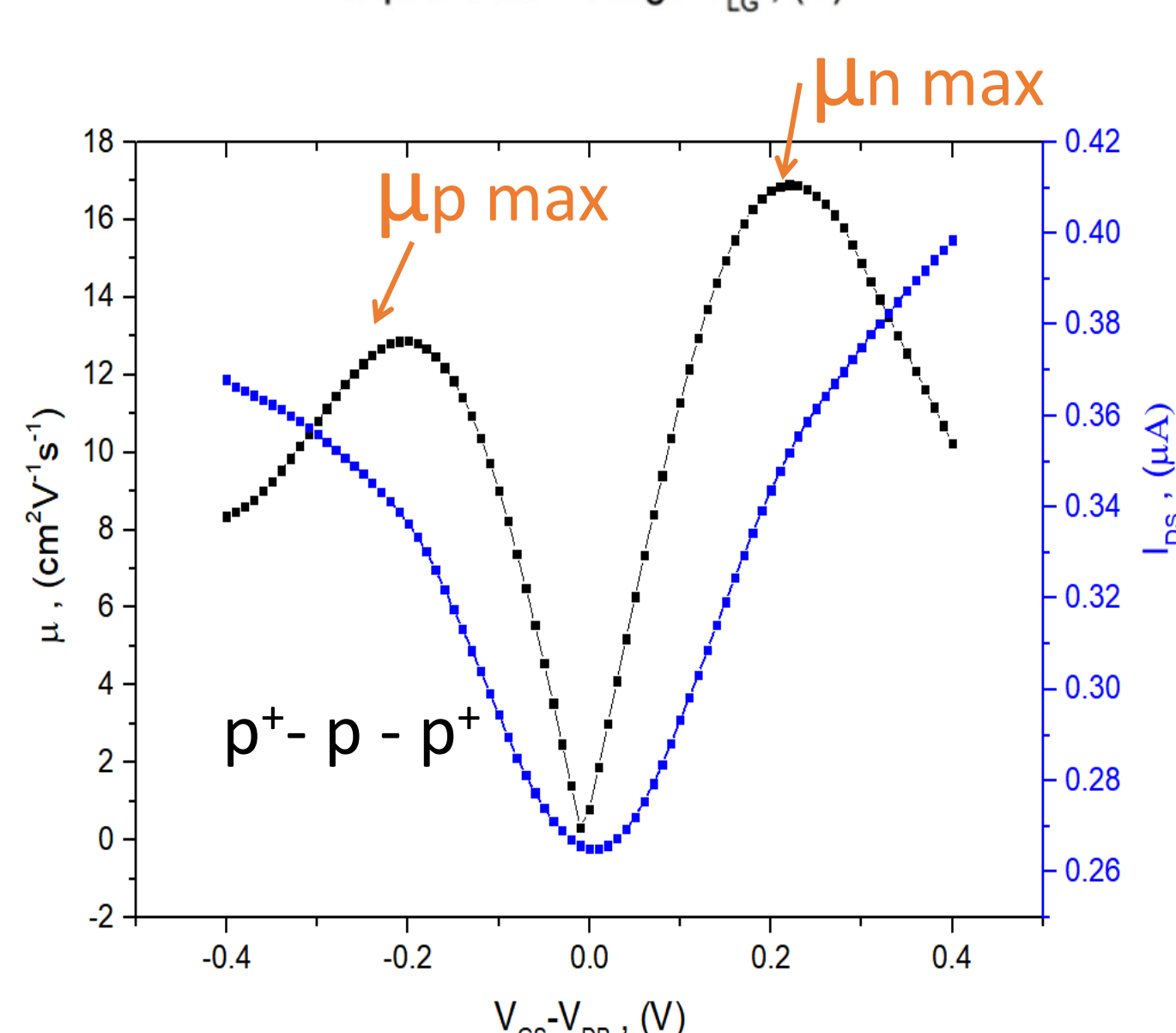
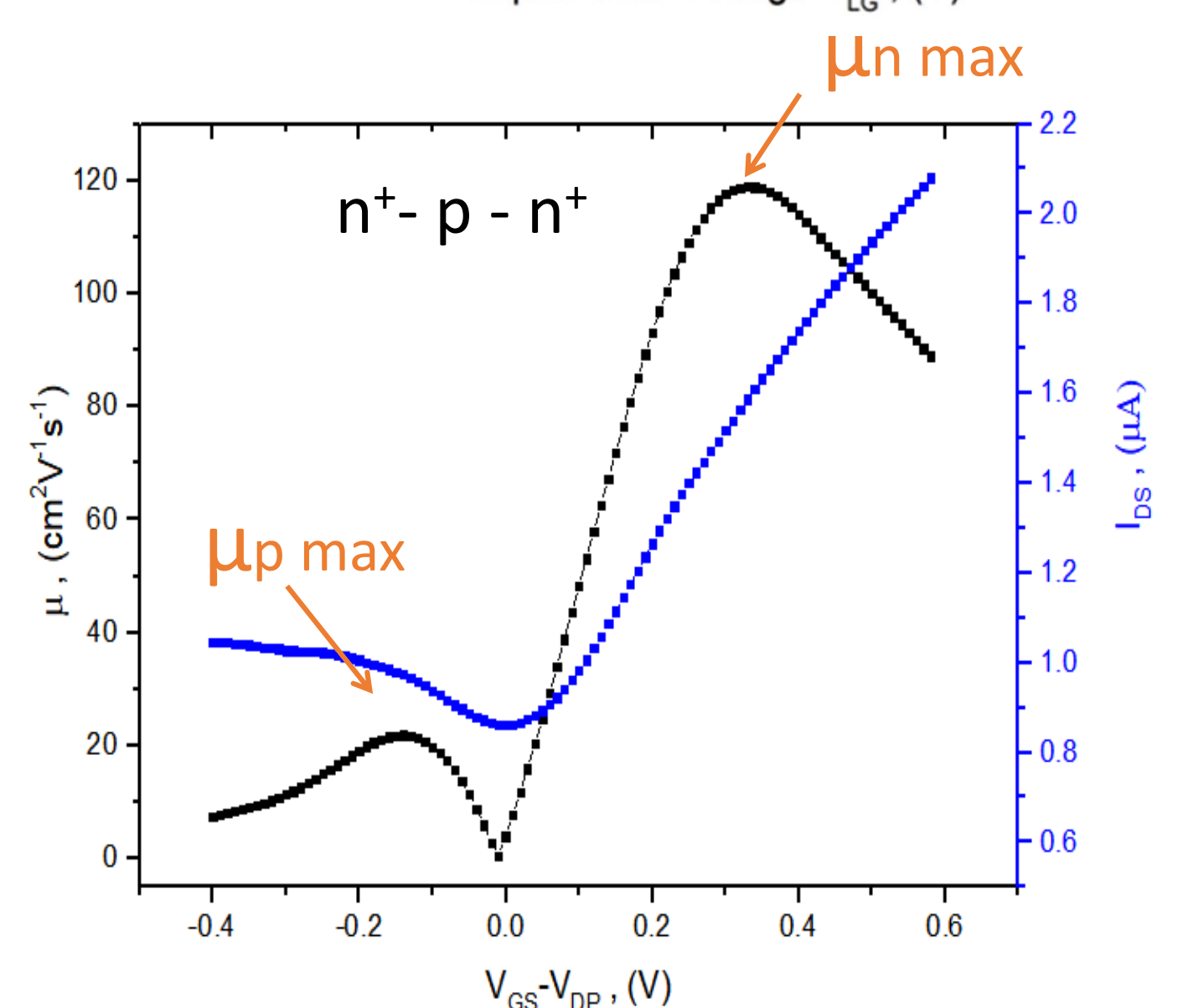


Transfer characteristics of hybrid GoSFETs with a different types of doping of drain and source regions: **n⁺-p-n⁺** and **p⁺-p-p⁺**.

The principle of work such devices is based on the parallel involvement of materials in charge transfer.

$$\mu = \frac{L}{W} \cdot \frac{g}{C_{ox} V_{DS}}$$

The estimated carriers mobility for liquid-gated FET structures reflects scattering on charged impurities [4] introduced in the native SiO₂ dielectric material due to the technological peculiarities of the devices.



Extraction of mobility for liquid-gated GoS-FET is a challenge, which requires consideration of several capacitances.

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Conclusions

- Established and optimized fabrication technology for new Graphene-on-Silicon field-effect transistors
- Dirac point and threshold voltage are well separated in p⁺-p-p⁺ structures. These results open prospects for high-sensitive biosensing applications.
- A new working principle of the hybrid device functionality based on the parallel involvement of materials in charge transfer is described.

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